



PATENT AND TRADEMARK OFFICE
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
(Use several sheets if necessary)

Atty Docket: A10CHI P103USP2
Examiner: John Joffmann
Group: 1731
Applicant: Akira IKUSHIMA, Kazuya SAITO, Takashi MIURA and Shogo NASUDA

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Examiner

Date Considered

2-19-01

No file

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